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Presented at Mirror Technology Days, Boulder, Colorado, USA, 7-9 June 2010.

14 ABSTRACT

Anti-reflective (AR) coatings comprised of several layers of oxide and nitride dielectric materials have successfully been sputter deposited on UV transparent polymethylmethacrylate (UVT-PMMA) windows. The amorphous coatings are deposited using reactive sputtering in a custom-designed magnetron sputtering tool. The AR coatings are adherent, radiation hard, and improve the transmission of UVT-PMMA windows by approximately 5% in the 300-450 nm range. The coatings will be applied and tested on UVT-PMMA Fresnel lenses for use in space-borne telescopes.

15. SUBJECT TERMS

Anti-reflective coatings, Fresnel lens, polymethylmethacrylate, PMMA

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<u>NanΩhmics</u>



Multilayer Anti-Reflective Coating Development for PMMA Fresnel Lenses

Don Patterson, Keith Jamison, and Byron Zollars

Mirror Technology SBIR/STTR Workshop

Boulder, CO June 7, 2009



Radiation Hard Multilayer Optical Coatings

SBIR Phase II Contract

NNX09CB36C

COTR: Bill Jones

Marshall Space Flight Center

Space ready multi-layer optical coatings

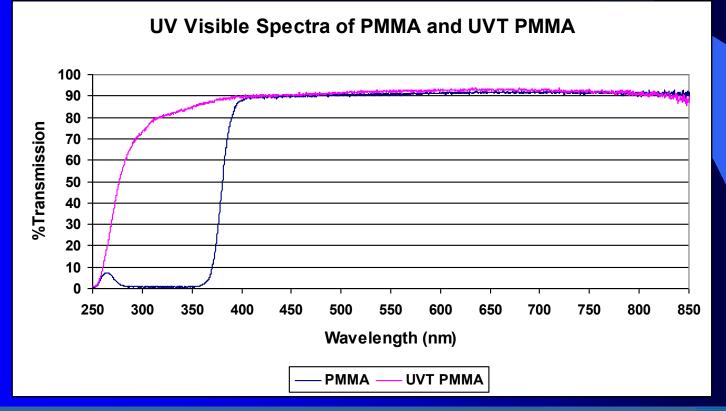
Problem: New optical coatings need to be developed for next generation light weight space base optics for use in programs such as NASA's EUSO observatory

Phase II Goal: Develop a robust anti-reflective coating that can be applied to UVT-PMMA Fresnel lenses

Nanohmics' Approach: Multi-layer amorphous nitrides / oxides as optical coating

Why PMMA?

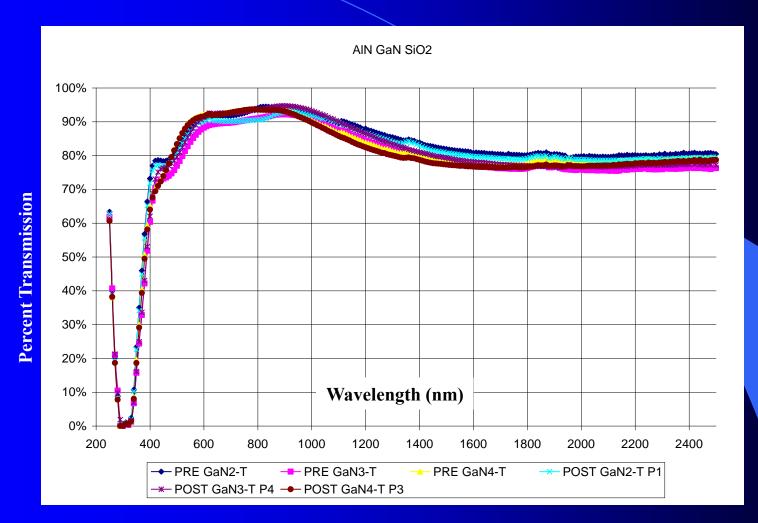
- Light weight
- UV Resistant
- UV Transparent
- Inexpensive



Advantages of Amorphous Oxides and Nitrides

- Proven radiation resistance to darkening
- Can be used to design anti-reflection, reflective, and band pass coatings
- Room temperature deposition
- Adhere well to most materials
- Robust coating

Radiation Hardness

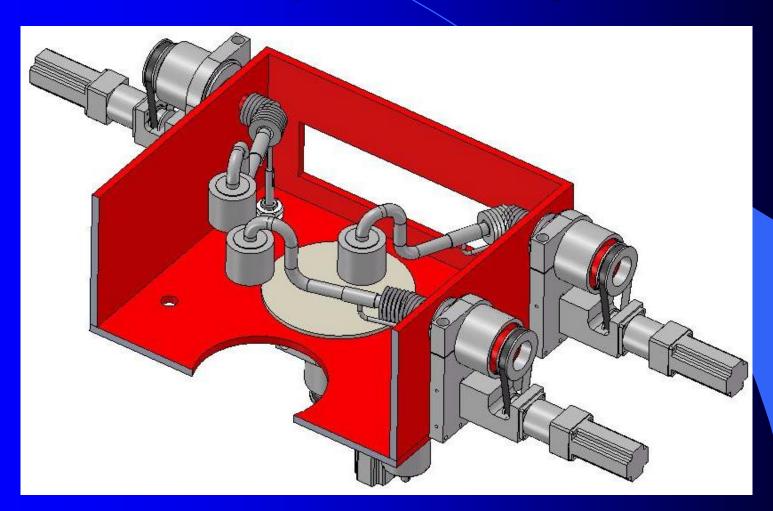


Multi-layer nitride / oxide coating exposed to ~ 10¹⁵ protons/cc flux at 20 keV, 50 keV, 100 keV and 300 keV

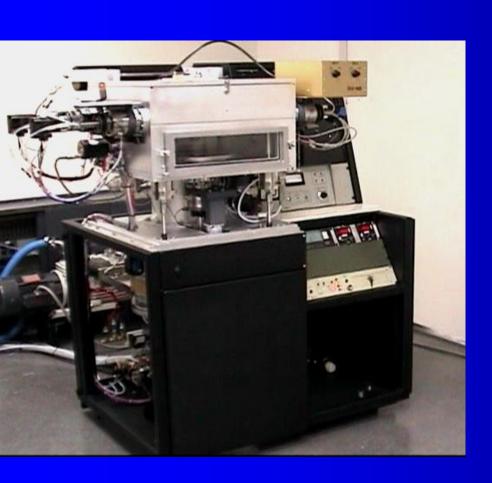
Advantages of Sputter Deposition

- Able to deposit optical quality films
- Reactive growth of nitrides and oxides results in relatively fast deposition rates
- Sputter process results in higher density, better adhesion coatings compared to e-beam deposition
 - Bias sample if increased density desired
- Deposit on cooled substrates
- Large established infrastructure
- Relatively inexpensive process that can handle large substrates (12" dia. in our system)

New Deposition System



Sputter Deposition System





Amorphous Nitride / Oxide Growth

- Coating materials: AlN, ZrO₂, and SiO₂
- All materials grown using reactive sputtering
 - Solid target (Al, Zr, Si)
 - Background gas (Ar:O₂ or Ar:N₂)
- RF power = 200 W
- Growth rates ~1.7-7.7 nm/min
- Thickness measured using optical methods (Filmetrics F20) and profilometry (Dektak)
- No delamination noted after thermal cycling (-55 C to 75 C)

Growth Rate and Adhesion Strength

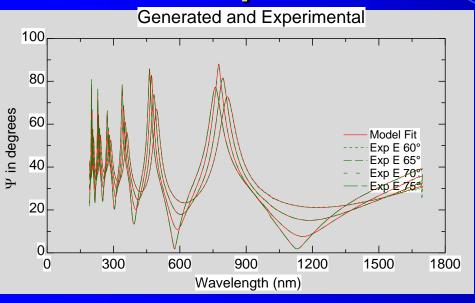
Growth rate of SiO₂, AlN, and ZrO₂ at 200 W RF power.

Material	Growth Rate
SiO ₂	7.7 nm/min
AIN	2.4 nm/min
ZrO ₂	1.7 nm/min

Adhesion strength to PMMA

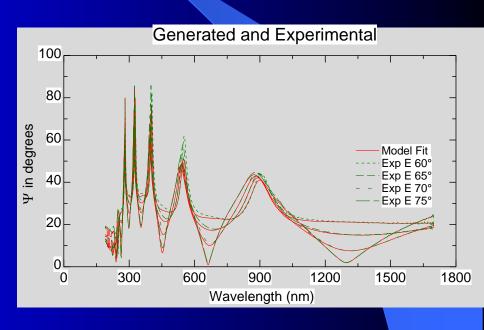
	AlN	SiO ₂	ZrO ₂
Max Adhesion Force (Kg)	4.7	3.0	1.0
Max Adhesion Strength (Kg/cm²)	83	52	18

Optical Constant Data



SiO₂

- At 500 nm:
 - AlN (n=1.973, k=0.0004)
 - ZrO_2 (n=2.10, k=0.0002)
 - SiO_2 (n=1.47, k=0.0007)



AlN

Stress

AR Coatings at 200 W; 500x magnification



Old System

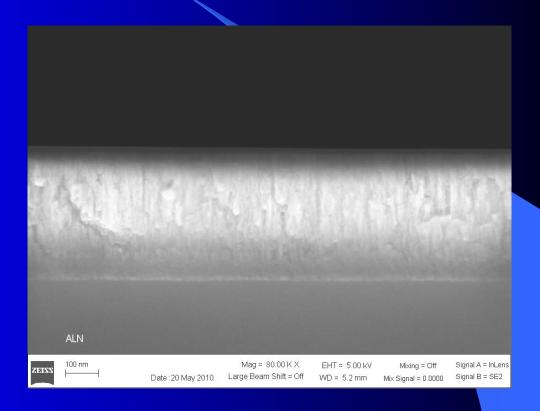


New System

Amorphous Films



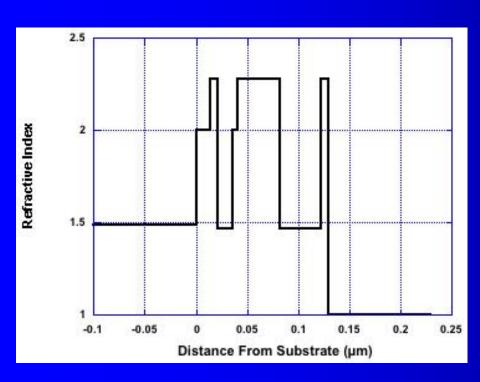
Old System

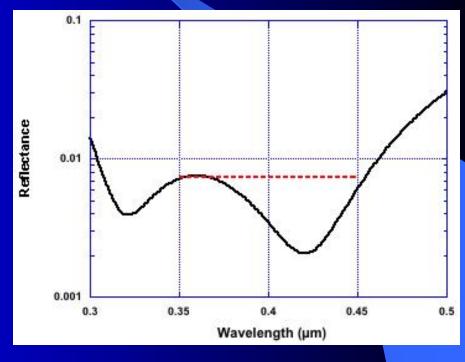


New System

Anti-Reflective Coating Model

SiO₂, AlN, and ZrO₂

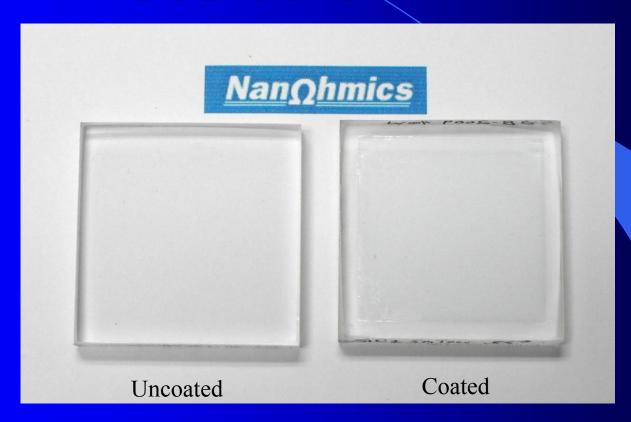




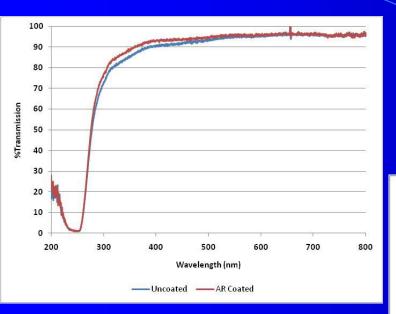
Prescription

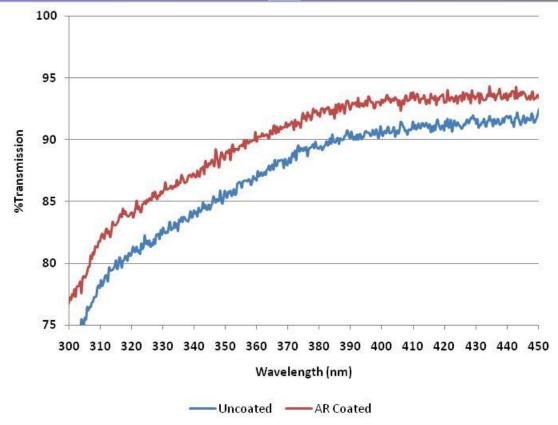
Anticipated Spectrum

AR Coated UVT PMMA



AR Coated UVT PMMA







Current Status / Results

- Designed and implemented new deposition
- Measured n and k for amorphous materials
- Stress eliminated in the films
- Initial AR coatings look promising



Future Work

- Improve models with new data
- Qualify new deposition tool
 - Deposition parameters
 - Coating uniformity (now at 90% uniformity)
- Deposition on Fresnel lenses
- Environmental Testing
 - Humidity
 - Temperature cycling
 - UV exposure

Small Business Innovation Research

Multilayer Anti-Reflective Coating Development For PMMA Fresnel Lenses

Nanohmics, Inc. Austin, TX

INNOVATION

Nanohmics is developing a robust, radiation-hard, antireflective coating for use on polymeric Fresnel lenses.

ACCOMPLISHMENTS

- Novel deposition system designed, fabricated, and implemented
- Low stress, high quality dielectric materials deposited on a variety of substrates including polymethylmethacrylate (PMMA)
- Highly amorphous films achieved
- Excellent adhesion to most materials
- 90% uniformity achieved

COMMERCIALIZATION

- Primary markets for the coatings include optics, tooling, and ceramics.
- Presently using the technology to increase the strength of ceramic drilling materials.
- ◆ Sales from the technology have reached \$12,500. If successful, a revenue stream of 2% gross is expected from our partner.
- Exploring partnerships with optics manufacturers.



AR Coated PMMA Fresnel Lens

GOVERNMENT/SCIENCE APPLICATIONS

- Technology being developed for use in the Extreme Universe Space Observatory (EUSO).
- Coatings still must be fully tested.
- Technology can be used for any number of robust, hard coatings especially for optical materials.
- Polymeric lenses will result in a lower launch weight and enhanced savings over using glass lenses.

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